

IN THE CLAIMS:

Please AMEND claim 1, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

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1. (Currently Amended) A projection exposure apparatus comprising:

a projection optical system ~~for projecting~~ arranged to project a pattern ~~on~~ onto a substrate;

a holding portion ~~for holding~~ arranged to hold an optical element which propagates light toward said projection optical system;

a mask ~~which is arranged~~ having a transmission portion and being disposed on or near an image plane or object plane of said projection optical system or a plane conjugate to the image plane and the object plane and has a transmission portion;

an actuator ~~for driving~~ arranged to drive said mask along a plane of an image of said optical element formed by said projection optical system; and

a measurement device ~~for measuring~~ arranged to measure an intensity of light ~~which emerges while said mask is driven,~~ the light emerging from said optical element, and ~~passes passing~~ through said projection optical system and the transmission portion of said mask, ~~while said mask is driven~~ said measurement device including a measurement surface positioned at a plane conjugate to a pupil plane of said projection optical system or a plane spaced apart from said mask enough to separately detect respective rays emerging from plural points of the pupil plane and passing through the transmission portion.

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2. (Original) The apparatus according to claim 1, further comprising an arithmetic device for calculating aberration of said projection optical system on the basis of a measurement result of said measurement device.

3. (Original) The apparatus according to claim 1, further comprising an arithmetic device for calculating ray aberration of said projection optical system on the basis of a measurement result of said measurement device.

4. (Original) The apparatus according to claim 1, further comprising an arithmetic device for calculating wavefront aberration of said projection optical system on the basis of a measurement result of said measurement device.

5. (Original) The apparatus according to claim 1, wherein
said optical element is arranged near the object plane of said projection optical system, and
said mask is arranged near the image plane of said projection optical system.

6. (Original) The apparatus according to claim 5, wherein
said optical element includes a mask having a transmission portion, and
light is emitted toward said projection optical system by illuminating said mask serving as said optical element by an illumination system.

7. (Original) The apparatus according to claim 1, wherein
said optical element is arranged near the image plane of said projection optical
system, and
said mask is arranged near the object plane of said projection optical system.

8. (Original) The apparatus according to claim 7, wherein
said optical element includes a mask having a transmission portion, and
light is emitted toward said projection optical system by illuminating said mask
serving as said optical element by an illumination system.

9. (Original) The apparatus according to claim 7, wherein
the projection exposure apparatus further comprises an illumination system,
said optical element includes a reflecting member, and
said reflecting member reflects, toward said projection optical system, light which
is emitted by said illumination system and is incident on said reflecting member via said
projection optical system.

10. (Original) The apparatus according to claim 9, further comprising a reflecting mirror
for deflecting light which emerges from said optical element and passes through said projection
optical system, and guiding the light to said mask.

11. (Original) The apparatus according to claim 1, wherein
said optical element is arranged near the object plane of said projection optical system,
said mask is arranged near a plane conjugate to the object plane of said projection optical system,
the projection exposure apparatus further comprises a first reflecting mirror arranged on the image plane side of said projection optical system, and a second reflecting mirror for reflecting, toward said measurement devices, light which is reflected by said first reflecting mirror and passes through said projection optical system, and
light which emerges from said optical element passes through said projection optical system, is reflected by said first reflecting mirror, passes through said projection optical system again, is reflected by said second reflecting mirror, and guided to said mask.

12. (Original) The apparatus according to claim 1, wherein
said optical element and said mask are arranged near the object plane of said projection optical system,
the projection exposure apparatus further comprises a reflecting mirror arranged on the image plane side of said projection optical system, and
light which emerges from said optical element passes through said projection optical system, is reflected by said reflecting mirror, passes through said projection optical system again, and is guided to said mask.

13. (Original) The apparatus according to claim 1, wherein
said optical element and said mask are arranged near the image plane of said
projection optical system,
the projection exposure apparatus further comprises a reflecting mirror arranged
on the object plane side of said projection optical system, and
light which emerges from said optical element passes through said projection
optical system, is reflected by said reflecting mirror, passes through said projection optical
system again, and is guided to said mask.

14. (Original) The apparatus according to claim 1, wherein a predetermined region near
the image plane or object plane of said projection optical system falls within an isoplanatic
region of said projection optical system.

15. (Original) The apparatus according to claim 1, wherein light which emerges from a
predetermined region near the image plane or object plane of said projection optical system
sufficiently covers a pupil of said projection optical system.

16. (Original) A projection exposure apparatus comprising:
an illumination system;
a projection optical system for projecting a pattern on a substrate;

a holding portion for holding a first mask having a first transmission portion between said illumination system and said projection optical system;

a second mask which is arranged near an image-side focal position of said projection optical system and has a second transmission portion;

an actuator for driving said second mask along an image plane of said projection optical system; and

a measurement device for measuring a change in intensity of light which is emitted by said illumination system and passes through the first transmission portion, said projection optical system, and the second transmission portion while said second mask is driven.

17. (Original) The apparatus according to claim 16, further comprising an arithmetic device for calculating aberration of said projection optical system on the basis of a measurement result of said measurement device.

18. (Original) The apparatus according to claim 16, further comprising an arithmetic device for calculating ray aberration of said projection optical system on the basis of a measurement result of said measurement device.

19. (Original) The apparatus according to claim 16, further comprising an arithmetic device for calculating wavefront aberration of said projection optical system on the basis of a measurement result of said measurement device.

20. (Original) The apparatus according to claim 16, further comprising an imaging optical system for imaging an exit pupil of said projection optical system on a measurement surface of said measurement device.


21. (Original) The apparatus according to claim 20, wherein said actuator drives said measurement device and said imaging optical system together with said second mask.

22. (Original) The apparatus according to claim 20, wherein
said second mask, said imaging optical system, and said measurement device
constitute an integral measurement unit, and
said actuator drives said measurement unit along the image plane of said
projection optical system.

23. (Original) The apparatus according to claim 16, wherein said first mask has a plurality of first transmission portions.

24. (Original) The apparatus according to claim 16, wherein said first mask has a transfer pattern to be transferred to the substrate, in addition to the first transmission portion.

25. (Original) A projection exposure apparatus comprising:
an illumination system;



a projection optical system for projecting a pattern on a substrate;
a first holding portion for holding a first mask having a first transmission portion between said illumination system and said projection optical system;
a first reflecting mirror arranged on an image plane side of said projection optical system;
a second mask which is arranged between said illumination system and said projection optical system and has a second transmission portion;
a second reflecting mirror for deflecting, toward the second transmission portion, light which is emitted by said illumination system, passes through the first transmission portion and said projection optical system, is reflected by said first reflecting mirror, and passes through said projection optical system again;
an actuator for driving said second mask in a predetermined plane; and
a measurement device for measuring an intensity of light which is emitted by said illumination system, passes through the first transmission portion of said first mask and said projection optical system, is reflected by said first reflecting mirror, passes through said projection optical system again, is reflected by said second reflecting mirror, and passes through the second transmission portion of said second mask while said second mask is driven.

26. (Original) The apparatus according to claim 25, further comprising an arithmetic device for calculating aberration of said projection optical system on the basis of a measurement result of said measurement device.

27. (Original) The apparatus according to claim 25, further comprising an arithmetic device for calculating ray aberration of said projection optical system on the basis of a measurement result of said measurement device.

28. (Original) The apparatus according to claim 25, further comprising an arithmetic device for calculating wavefront aberration of said projection optical system on the basis of a measurement result of said measurement device.

29. (Original) The apparatus according to claim 25, wherein said first reflecting mirror includes a spherical mirror.

30. (Original) The apparatus according to claim 25, wherein said second reflecting mirror includes a half-mirror which transmits light emitted by said illumination system toward said projection optical system, and reflects, toward the second transmission portion of said second mask, light which is reflected by said first reflecting mirror and passes through said projection optical system.

31. (Original) A projection exposure apparatus comprising:

an illumination system;

a projection optical system for projecting a pattern on a substrate;

a holding portion for holding a first mask having a first transmission portion between said illumination system and said projection optical system;

a second mask which is arranged near an object plane of said projection optical system and has a second transmission portion;

a reflecting mirror arranged on an image plane side of said projection optical system, light which is emitted by said illumination system, passes through the first transmission portion and said second projection optical system, is reflected by said reflecting mirror, and passes through said projection optical system again being incident on the second transmission portion;

an actuator for driving said second mask along the object plane of said projection optical system; and

a measurement device for measuring an intensity of light which is emitted by said illumination system, passes through the first transmission portion and said projection optical system, is reflected by said reflecting mirror, passes through said projection optical system again, and passes through the second transmission portion while said second mask is driven.

32. (Original) The apparatus according to claim 31, further comprising an arithmetic device for calculating aberration of said projection optical system on the basis of a measurement result of said measurement device.

33. (Original) The apparatus according to claim 31, further comprising an arithmetic device for calculating ray aberration of said projection optical system on the basis of a measurement result of said measurement device.

34. (Original) The apparatus according to claim 31, further comprising an arithmetic device for calculating wavefront aberration of said projection optical system on the basis of a measurement result of said measurement device.

35. (Original) The apparatus according to claim 31, wherein said reflecting mirror includes a spherical mirror.

36. (Original) A projection exposure apparatus comprising:

- a substrate stage;
- a projection optical system for projecting a pattern on a substrate on said substrate stage;
- a first mask which is arranged between said projection optical system and said substrate stage and has a first transmission portion;
- an illumination system for illuminating the first transmission portion;
- a second mask which is arranged between said projection optical system and said substrate stage and has a second transmission portion;

a reflecting mirror arranged on an object side of said projection optical system, light which is emitted by said illumination system, passes through the first transmission portion and said projection optical system, is reflected by said reflecting mirror, and passes through said projection optical system again being incident on the second transmission portion;

an actuator for driving said second mask along an image plane of said projection optical system; and

a measurement device for measuring an intensity of light which is emitted by said illumination system, passes through the first transmission portion and said projection optical system, is reflected by said reflecting mirror, passes through said projection optical system again, and passes through the second transmission portion while said second mask is driven.

37. (Original) The apparatus according to claim 36, further comprising an arithmetic device for calculating aberration of said projection optical system on the basis of a measurement result of said measurement device.

38. (Original) The apparatus according to claim 36, further comprising an arithmetic device for calculating ray aberration of said projection optical system on the basis of a measurement result of said measurement device.

39. (Original) The apparatus according to claim 36, further comprising an arithmetic device for calculating wavefront aberration of said projection optical system on the basis of a measurement result of said measurement device.

40. (Original) The apparatus according to claim 36, wherein said reflecting mirror includes a spherical mirror.

41. (Original) A method of measuring aberration of a projection optical system in a projection exposure apparatus for projecting a pattern on a substrate via the projection optical system,

the projection exposure apparatus having

a projection optical system for projecting a pattern on a substrate,

a holding portion for holding an optical element which propagates light toward the projection optical system, and

a mask which is arranged near an image plane or object plane of the projection optical system or a plane conjugate to the image plane and object plane and has a transmission portion,

the method comprising:

the measurement step of measuring an intensity of light which emerges from the optical element, and passes through the projection optical system and the transmission portion of

the mask while the mask is driven along a plane of an image of the optical element formed by the projection optical system; and

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step.

42. (Original) A method of measuring aberration of a projection optical system in a projection exposure apparatus for projecting a pattern on a substrate via the projection optical system,

the projection exposure apparatus having

an illumination system,

a projection optical system for projecting a pattern on a substrate,

a holding portion for holding a first mask having a first transmission portion between the illumination system and the projection optical system, and

a second mask which is arranged near an image-side focal position of the projection optical system and has a second transmission portion,

the method comprising:

the measurement step of measuring a change in intensity of light which is emitted by the illumination system and passes through the first transmission portion, the projection optical system, and the second transmission portion while the second mask is driven along an image plane of the projection optical system; and

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step.

43. (Original) A method of measuring aberration of a projection optical system in a projection exposure apparatus for projecting a pattern on a substrate via the projection optical system,

the projection exposure apparatus having

an illumination system,

a projection optical system for projecting a pattern on a substrate,

a first holding portion for holding a first mask having a first transmission portion between the illumination system and the projection optical system;

a first reflecting mirror arranged on an image plane side of the projection optical system,

a second mask which is arranged between the illumination system and the projection optical system and has a second transmission portion, and

a second reflecting mirror for deflecting, toward the second transmission portion, light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the first reflecting mirror, and passes through the projection optical system again

the method comprising:

the measurement step of measuring an intensity of light which is emitted by the illumination system, passes through the first transmission portion of the first mask and the projection optical system, is reflected by the first reflecting mirror, passes through the projection optical system again, is reflected by the second reflecting mirror, and passes through the second transmission portion of the second mask while the second mask is driven in a predetermined plane; and

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step.

44. (Original) A method of measuring aberration of a projection optical system in a projection exposure apparatus for projecting a pattern on a substrate via the projection optical system,

the projection exposure apparatus having
an illumination system,
a projection optical system for projecting a pattern on a substrate,
a holding portion for holding a first mask having a first transmission portion
between the illumination system and the projection optical system,

a second mask which is arranged near an object plane of the projection optical system and has a second transmission portion, and

a reflecting mirror arranged on an image plane side of the projection optical system, light which is emitted by the illumination system, passes through the first transmission

portion and the projection optical system, is reflected by the reflecting mirror, and passes through the projection optical system again being incident on the second transmission portion

the method comprising:

the measurement step of measuring an intensity of light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the reflecting mirror, passes through the projection optical system again, and passes through the second transmission portion while the second mask is driven along the object plane of the projection optical system; and

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step.

45. (Original) A method of measuring aberration of a projection optical system in a projection exposure apparatus for projecting a pattern on a substrate via the projection optical system,

the projection exposure apparatus having

a substrate stage,

a projection optical system for projecting a pattern on a substrate on the substrate stage,

a first mask which is arranged between the projection optical system and the substrate stage and has a first transmission portion,

an illumination system for illuminating the first transmission portion,

a second mask which is arranged between the projection optical system and the substrate stage and has a second transmission portion, and

a reflecting mirror arranged on an object side of the projection optical system, light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the reflecting mirror, and passes through the projection optical system again being incident on the second transmission portion,

the method comprising:

the measurement step of measuring an intensity of light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the reflecting mirror, passes through the projection optical system again, and passes through the second transmission portion while the second mask is driven along an image plane of the projection optical system; and

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step.

46. (Original) A transfer method of transferring a pattern to a substrate by using a projection exposure apparatus,

the projection exposure apparatus having

a projection optical system for projecting a pattern on a substrate,

a holding portion for holding an optical element which propagates light toward the projection optical system, and

a mask which is arranged near an image plane or object plane of the projection optical system or a plane conjugate to the image plane and object plane and has a transmission portion,

the method comprising:

the measurement step of measuring an intensity of light which emerges from the optical element, and passes through the projection optical system and the transmission portion of the mask while the mask is driven along a plane of an image of the optical element formed by the projection optical system;

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step;

the adjustment step of adjusting the projection optical system on the basis of aberration obtained in the arithmetic step; and

the transfer step of transferring a pattern to the substrate by using the projection exposure apparatus in which the projection optical system is adjusted.

47. (Original) A transfer method of transferring a pattern to a substrate by using a projection exposure apparatus,

the projection exposure apparatus having

an illumination system,

a projection optical system for projecting a pattern on a substrate,

a holding portion for holding a first mask having a first transmission portion between the illumination system and the projection optical system, and

a second mask which is arranged near an image-side focal position of the projection optical system and has a second transmission portion,

the method comprising:

the measurement step of measuring a change in intensity of light which is emitted by the illumination system and passes through the first transmission portion, the projection optical system, and the second transmission portion while the second mask is driven along an image plane of the projection optical system;

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step; and

the transfer step of transferring a pattern to the substrate by using the projection exposure apparatus in which the projection optical system is adjusted.

48. (Original) A transfer method of transferring a pattern to a substrate by using a projection exposure apparatus,

the projection exposure apparatus having

an illumination system,

a projection optical system for projecting a pattern on a substrate,

a first holding portion for holding a first mask having a first transmission portion between the illumination system and the projection optical system;

a first reflecting mirror arranged on an image plane side of the projection optical system,

a second mask which is arranged between the illumination system and the projection optical system and has a second transmission portion, and

a second reflecting mirror for deflecting, toward the second transmission portion, light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the first reflecting mirror, and passes through the projection optical system again,

the method comprising:

the measurement step of measuring an intensity of light which is emitted by the illumination system, passes through a first transmission portion of the first mask and the projection optical system, is reflected by the first reflecting mirror, passes through the projection optical system again, is reflected by the second reflecting mirror, and passes through the second transmission portion of the second mask while the second mask is driven in a predetermined plane;

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step;

the adjustment step of adjusting the projecting optical system on the basis of aberration obtained in the arithmetic step; and

the transfer step of transferring a pattern to the substrate by using the projection exposure apparatus in which the projection optical system is adjusted.

49. (Original) A transfer method of transferring a pattern to a substrate by using a projection exposure apparatus,

the projection exposure apparatus having

an illumination system,

a projection optical system for projecting a pattern on a substrate,

a holding portion for holding a first mask having a first transmission portion between the illumination system and the projection optical system,

a second mask which is arranged near an object plane of the projection optical system and has a second transmission portion, and

a reflecting mirror arranged on an image plane side of the projection optical system, light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the reflecting mirror, and passes through the projection optical system again being incident on the second transmission portion

the method comprising:

the measurement step of measuring an intensity of light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the reflecting mirror, passes through the projection optical system again, and passes through the second transmission portion while the second mask is driven along the object plane of the projection optical system;

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step;

the adjustment step of adjusting the projection optical system on the basis of aberration obtained in the arithmetic step; and

the transfer step of transferring a pattern to the substrate by using the projection exposure apparatus in which the projection optical system is adjusted.

50. (Original) A transfer method of transferring a pattern to a substrate by using a projection exposure apparatus,

the projection exposure apparatus having

a substrate stage,

a projection optical system for projecting a pattern on a substrate on the substrate

stage,

a first mask which is arranged between the projection optical system and the substrate stage and has a first transmission portion,

an illumination system for illuminating the first transmission portion,

a second mask which is arranged between the projection optical system and the substrate stage and has a second transmission portion, and

a reflecting mirror arranged on an object side of the projection optical system, light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the reflecting mirror, and passes through the projection optical system again being incident on the second transmission portion,

the method comprising:

the measurement step of measuring an intensity of light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the reflecting mirror, passes through the projection optical system again, and passes through the second transmission portion while the second mask is driven along an image plane of the projection optical system;

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step;

the adjustment step of adjusting the projection optical system on the basis of aberration obtained in the arithmetic step; and

the transfer step of transferring a pattern to the substrate by using the projection exposure apparatus in which the projection optical system is adjusted.

51. (Original) A method of manufacturing a device by using a projection exposure apparatus,

the projection exposure apparatus having
a projection optical system for projecting a pattern on a substrate,
a holding portion for holding an optical element which propagates light toward the projection optical system, and

a mask which is arranged near an image plane or object plane of the projection optical system or a plane conjugate to the image plane and object plane and has a transmission portion,

the method comprising:

the measurement step of measuring an intensity of light which emerges from the optical element, and passes through the projection optical system and the transmission portion of the mask while the mask is driven along a plane of an image of the optical element formed by the projection optical system;

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step;

the adjustment step of adjusting the projection optical system on the basis of the aberration obtained in the arithmetic step;

the transfer step of transferring a pattern to a photosensitive member of the substrate coated with the photosensitive member by using the projection exposure apparatus in which the projection optical system is adjusted; and

the developing step of developing the photosensitive member bearing the pattern.

52. (Original) A method of manufacturing a device by using a projection exposure apparatus,

the projection exposure apparatus having

an illumination system,

a projection optical system for projecting a pattern on a substrate,

a holding portion for holding a first mask having a first transmission portion between the illumination system and the projection optical system, and

a second mask which is arranged near an image-side focal position of the projection optical system and has a second transmission portion,

the method comprising:

the measurement step of measuring a change in intensity of light which is emitted by the illumination system and passes through the first transmission portion, the projection optical system, and the second transmission portion while the second mask is driven along an image plane of the projection optical system;

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step;

the adjustment step of adjusting the projection optical system on the basis of the aberration obtained in the arithmetic step;

the transfer step of transferring a pattern to a photosensitive member of the substrate coated with the photosensitive member by using the projection exposure apparatus in which the projection optical system is adjusted; and

the developing step of developing the photosensitive member bearing the pattern.

53. (Original) A method of manufacturing a device by using a projection exposure apparatus,

the projection exposure apparatus having

an illumination system,

a projection optical system for projecting a pattern on a substrate,

a first holding portion for holding a first mask having a first transmission portion between the illumination system and the projection optical system,

a second mask which is arranged between the illumination system and the projection optical system and has a second transmission portion, and

a second reflecting mirror for deflecting, toward the second transmission portion, light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the first reflecting mirror, and passes through the projection optical system again,

the method comprising:

the measurement step of measuring an intensity of light which is emitted by the illumination system, passes through the first transmission portion of the first mask and the projection optical system, is reflected by the first reflecting mirror, passes through the projection optical system again, is reflected by the second reflecting mirror, and passes through the second transmission portion of the second mask while the second mask is driven in a predetermined plane;

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step;

the adjustment step of adjusting the projection optical system on the basis of the aberration obtained in the arithmetic step;

the transfer step of transferring a pattern to a photosensitive member of the substrate coated with the photosensitive member by using the projection exposure apparatus in which the projection optical system is adjusted; and

the developing step of developing the photosensitive member bearing the pattern.

54. (Original) A method of manufacturing a device by using a projection exposure apparatus,

the projection exposure apparatus having

an illumination system,

a projection optical system for projecting a pattern on a substrate,

a holding portion for holding a first mask having a first transmission portion between the illumination system and the projection optical system,

a second mask which is arranged near an object plane of the projection optical system and has a second transmission portion, and

a reflecting mirror arranged on an image plane side of the projection optical system, light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the reflecting mirror, and passes through the projection optical system again being incident on the second transmission portion,

the method comprising:

the measurement step of measuring an intensity of light which is emitted by the illumination system, passes through the first transmission portion and the projection optical

system, is reflected by the reflecting mirror, passes through the projection optical system again, and passes through the second transmission portion while the second mask is driven along the object plane of the projection optical system;

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step;

the adjustment step of adjusting the projection optical system on the basis of the aberration obtained in the arithmetic step;

the transfer step of transferring a pattern to a photosensitive member of the substrate coated with the photosensitive member by using the projection exposure apparatus in which the projection optical system is adjusted; and

the developing step of developing the photosensitive member bearing the pattern.

55. (Original) A method of manufacturing a device by using a projection exposure apparatus,

the projection exposure apparatus having

a substrate stage,

a projection optical system for projecting a pattern on a substrate on the substrate stage,

a first mask which is arranged between the projection optical system and the substrate stage and has a first transmission portion,

an illumination system for illuminating the first transmission portion,

a second mask which is arranged between the projection optical system and the substrate stage and has a second transmission portion, and

a reflecting mirror arranged on an object side of the projection optical system, light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the reflecting mirror, and passes through the projection optical system again being incident on the second transmission portion,

the method comprising:

the measurement step of measuring an intensity of light which is emitted by the illumination system, passes through the first transmission portion and the projection optical system, is reflected by the reflecting mirror, passes through the projection optical system again, and passes through the second transmission portion while the second mask is driven along an image plane of the projection optical system;

the arithmetic step of calculating aberration of the projection optical system on the basis of a measurement result obtained in the measurement step;

the adjustment step of adjusting the projection optical system on the basis of the aberration obtained in the arithmetic step;

the transfer step of transferring a pattern to a photosensitive member of the substrate coated with the photosensitive member by using the projection exposure apparatus in which the projection optical system is adjusted; and

the developing step of developing the photosensitive member bearing the pattern.